

wherein, for the purpose of producing the at least one functional surface, a layer comprising nickel is deposited first and a layer of gold is applied there onto; wherein the at least one functional surface is formed by the deposition of at least one functional layer by means of chemical reduction or cementation; wherein the covering mask is formed by performing the following steps:

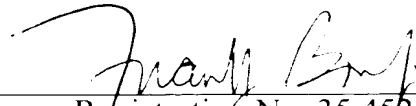
- (c1) application of a layer of photoresist,
- (c2) exposure of the layer of photoresist with a model of the mask in such a manner that the function regions can be led bare in a subsequent development stage and
- (c3) development of the exposed layer of photoresist. --

REMARKS

Applicant respectfully requests entry of the foregoing preliminary amendment which is being filed with the application.

The Commissioner is authorized to charge any additional fees which may be required to Patent Office Deposit Account No. 05-0208.

Respectfully submitted,
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